

PATENT
0171-1045P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: KANEKO, Hideo et al Conf.:
Appl. No.: NEW Group:
Filed: December 2, 2003 Examiner:
For: METHODS OF MANUFACTURING PHOTOMASK BLANK
AND PHOTOMASK

PRELIMINARY AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

December 2, 2003

Sir:

The following preliminary amendments and remarks are respectfully submitted in connection with the above-identified application.

This amendment includes Amendments to the Specification and Remarks.